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Laser Applications in Microelectronic and Optoelectronic Manufacturing (LAMOM) XVII

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Contents

ix Conference Committee

SESSION 1 DIRECT WRITING

- 8243 03 **Picosecond fiber laser microfabrication of THz wire-grid polarizers on polymer membrane substrates** [8243-02]
T. D. Gerke, Fiamium Inc. (United States); D. Fast, V. G. Kozlov, Microtech Instruments, Inc. (United States)
- 8243 04 **Laser direct writing of high-refractive-index polymer/TiO₂ nanocomposites** [8243-03]
Q. Guo, R. Ghadiri, S. Xiao, C. Esen, O. Medenbach, A. Ostendorf, Ruhr-Univ. Bochum (Germany)
- 8243 05 **Bimetallic grayscale photomasks written using flat-top beam vs. Gaussian beam** [8243-04]
R. Qarehbaghi, G. H. Chapman, W. Boonyasiriwat, Simon Fraser Univ. (Canada)

SESSION 2 FUNDAMENTAL ASPECTS OF LASER-MATERIAL INTERACTION

- 8243 07 **Optimization of the volume ablation rate for metals at different laser pulse-durations from ps to fs** [8243-06]
B. Neuenschwander, B. Jaeggi, M. Schmid, Bern Univ. of Applied Science (Switzerland); V. Roufflange, Amplitude Systemes (France); P.-E. Martin, Lasea S.A. (Belgium)
- 8243 08 **Time- and space-resolved microscopy of induced ablation with ultra-short laser pulses** [8243-07]
M. Domke, S. Rapp, G. Heise, H. P. Huber, Munich Univ. of Applied Sciences (Germany)
- 8243 0A **Laser ablation plasmas for diagnostics of structured electronic and optical materials during or after laser processing** [8243-10]
R. E. Russo, Lawrence Berkeley National Lab. (United States) and Applied Spectra, Inc. (United States); A. A. Bol'shakov, J. H. Yoo, Applied Spectra, Inc. (United States); J. J. González, Lawrence Berkeley National Lab. (United States) and Applied Spectra, Inc. (United States)

SESSION 3 LASER MODIFICATION OF MATERIALS

- 8243 0C **Annealing of sol-gel derived metal-oxide thin films by a UV laser pulse train** [8243-12]
J. Zhang, Panasonic Boston Lab. (United States)
- 8243 0E **Laser-induced transient stress distribution inside a single crystal by time-resolved birefringence imaging** [8243-14]
T. Tochio, M. Sakakura, S. Kanehira, Y. Shimotsuma, K. Miura, K. Hirao, Kyoto Univ. (Japan)

SESSION 4 LASER NANOSCALE MATERIALS PROCESSING AND MANUFACTURING: JOINT SESSION WITH CONFERENCE 8245

- 8243 OF **Surface plasmon-assisted nanolithography with nanometric accuracy (Invited Paper)** [8243-15]
K. Ueno, Hokkaido Univ. (Japan) and PRESTO, Japan Science and Technology Agency (Japan); H. Misawa, Hokkaido Univ. (Japan)

SESSION 5 ULTRAFAST LASER 3D-FABRICATION: JOINT SESSION WITH CONFERENCE 8247

- 8243 0I **Applications of picosecond lasers and pulse-bursts in precision manufacturing (Invited Paper)** [8243-18]
R. Knappe, LUMERA LASER GmbH (Germany)
- 8243 0J **High-sensitive concentration analysis of biochemical liquids using a microfluidic chip fabricated by femtosecond laser** [8243-19]
Y. Hanada, K. Sugioka, K. Midorikawa, RIKEN (Japan)
- 8243 0K **Ultra-high-precision surface structuring by synchronizing a galvo scanner with an ultra-short-pulsed laser system in MOPA arrangement** [8243-20]
B. Jaeggi, B. Neuenschwander, U. Hunziker, J. Zuercher, T. Meier, M. Zimmermann, K. H. Selbmann, Bern Univ. of Applied Sciences (Switzerland); G. Hennig, Daetwyler Graphics AG (Switzerland)

SESSION 6 ULTRAFAST LASER-INDUCED MODIFICATION OF GLASSES OR TRANSPARENT MATERIALS: JOINT SESSION WITH CONFERENCE 8247

- 8243 0M **Machining of glass and quartz using nanosecond and picosecond laser pulses** [8243-23]
D. Ashkenasi, T. Kaszemeikat, N. Mueller, A. Lemke, Laser- und Medizin-Technologie GmbH, Berlin (Germany); H. J. Eichler, Laser- und Medizin-Technologie GmbH, Berlin (Germany) and Technische Univ. Berlin (Germany)
- 8243 0N **Fabrication of photo-induced microstructure embedded inside ZnO crystal** [8243-24]
Y. Ishikawa, Y. Shimotsuma, A. Kaneta, M. Sakakura, M. Nishi, K. Miura, K. Hirao, Y. Kawakami, Kyoto Univ. (Japan)

SESSION 7 ULTRAFAST LASER SURFACE PROCESSING: JOINT SESSION WITH CONFERENCE 8247

- 8243 0O **Comparison of picosecond and femtosecond laser ablation for surface engraving of metals and semiconductors** [8243-25]
J. Lopez, ALPhANOV (France) and Univ. de Bordeaux (France); R. Kling, R. Torres, A. Lidolff, ALPhANOV (France); M. Delaigue, S. Ricaud, C. Hönniger, E. Mottay, Amplitude Systemes (France)
- 8243 0P **Pulsed fiber laser texturing of metals, silicon, and ceramics: comparison of surface structural changes induced by ns and fs pulses** [8243-26]
S. T. Hendow, Multiwave Photonics (Portugal); A. M. Ozkan, Lumyn Technologies LLC (United States); M. Oliveira, INEGI (Portugal); E. Mottay, Amplitude Systemes (France)

SESSION 8 FUNDAMENTALS AND DIAGNOSTICS IN ULTRAFAST LASER PROCESSING: JOINT SESSION WITH CONFERENCE 8247

- 8243 OS **Direct investigation of the ablation rate evolution during laser drilling of high-aspect-ratio micro-holes** [8243-29]

F. P. Mezzapesa, Univ. degli Studi di Bari (Italy) and CNR-IFN UOS Bari (Italy); T. Sibillano, L. L. Columbo, CNR-IFN UOS Bari (Italy); F. Di Niso, Univ. degli Studi di Bari (Italy); A. Ancona, CNR-IFN UOS Bari (Italy); M. Dabbiacco, Univ. degli Studi di Bari (Italy) and CNR-IFN UOS Bari (Italy); F. De Lucia, Univ. degli Studi di Bari (Italy); P. M. Lugarà, G. Scamarcio, Univ. degli Studi di Bari (Italy) and CNR-IFN UOS Bari (Italy)

SESSION 9 LASER SURFACE TEXTURING/POLISHING

- 8243 0U **Periodic nano trench structure fabricated by high-speed scanning CW laser** [8243-31]
S. Kaneko, Kanagawa Industrial Technology Ctr. (Japan) and Tokyo Institute of Technology (Japan); T. Ito, M. Yasui, C. Kato, S. Tanaka, T. Ozawa, Y. Hirabayashi, Kanagawa Industrial Technology Ctr. (Japan); A. Matsuno, T. Nire, Phoeton Corp. (Japan); M. Yoshimoto, Tokyo Institute of Technology (Japan)

- 8243 0W **Laser polishing** [8243-33]
A. Temmler, RWTH Aachen (Germany); E. Willenborg, K. Wissenbach, Fraunhofer Institute for Lasertechnology (Germany)

SESSION 10 LASER SURFACE TEXTURING AND 3D MICROSTRUCTURING

- 8243 0X **Formation of tribological structures by laser ablation** [8243-34]
N. Schilling, M. Paschke, Fraunhofer IWS Dresden (Germany); S. T. Hendow, Multiwave Photonics (Portugal); U. Klotzbach, Fraunhofer IWS Dresden (Germany)

- 8243 0Y **Laser-induced front side etching of fused silica with short and ultra-short laser pulses** [8243-35]
P. Lorenz, M. Ehrhardt, K. Zimmer, Leibniz-Institut für Oberflächenmodifizierung e.V. (Germany)

- 8243 0Z **Facile and flexible fabrication of gapless microlens arrays using a femtosecond laser microfabrication and replication process** [8243-36]
H. Liu, F. Chen, Q. Yang, Y. Hu, C. Shan, S. He, J. Si, X. Hou, Xi'an Jiaotong Univ. (China)

SESSION 11 NOVEL LASER SYSTEMS AND OPTICS FOR LASER MICRO/NANOMACHINING

- 8243 10 **Control of material properties by parallel laser irradiations at multiple laser spots using a spatial light modulator (Invited Paper)** [8243-37]
M. Sakakura, T. Tochio, M. Shimizu, N. Yasuda, Kyoto Univ. (Japan); M. Ohnishi, Futaku Precision Machinery Industry Co. (Japan); K. Miura, Y. Shimotsuma, K. Hirao, Kyoto Univ. (Japan)

- 8243 11 **Green line-shaped focus and multiple-foci geometry for photovoltaic manufacturing and other applications on silicon** [8243-38]
M. Ivanenko, K. Bagschik, W. Grimm, A. Krasnaberski, LIMO Lissotschenko Mikrooptik GmbH (Germany)
- 8243 12 **Investigation of micro lens multi spot generator for parallel micromachining of silicon with picosecond and nanosecond laser** [8243-39]
M. Zimmermann, S. Roth, BLZ Bayerisches Laserzentrum GmbH (Germany) and Friedrich-Alexander-Univ. Erlangen-Nürnberg (Germany)
- 8243 14 **New nanosecond Q-switched 213 and 224nm lasers for fiber Bragg grating inscription in hydrogen-free fibers** [8243-41]
M. Gagné, R. Kashyap, Ecole Polytechnique de Montréal (Canada)

SESSION 12 PHOTOVOLTAICS: JOINT SESSION WITH CONFERENCE 8244

- 8243 16 **Structuring of functional thin films and surfaces with picosecond-pulsed lasers (Invited Paper)** [8243-43]
G. Račiukaitis, P. Gečys, M. Gedvilas, B. Voisiat, Ctr. for Physical Sciences and Technology (Lithuania)
- 8243 17 **Laser processes for future solar cells (Invited Paper)** [8243-44]
A. Letsch, D. Bartl, M. Diez, R. Gauch, A. Michalowski, Robert Bosch GmbH (Germany); M. Hafner, Univ. of Stuttgart (Germany)
- 8243 18 **Selective ablation of thin films in latest generation CIGS solar cells with picosecond pulses** [8243-45]
A. Burn, V. Romano, M. Muralt, Bern Univ. of Applied Sciences (Switzerland); R. Witte, B. Frei, Solneva SA (Switzerland); S. Bücheler, S. Nishiwaki, EMPA (Switzerland)

POSTER SESSION

- 8243 19 **Development of laser-based application system with high precision and speed** [8243-46]
K. Ryu, S. Shin, H. Park, T. Hwang, ASTJETEC Co., Ltd. (Korea, Republic of)
- 8243 1A **Reproduction of a unit of power of the laser radiation in compliance with the redefinition of the optical watt** [8243-47]
J. Owsik, Military Univ. of Technology (Poland); A. A. Liberman, A. A. Kovalev, S. A. Moskalyuk, All-Russia Research Institute of Optical and Physical Measurements (Russian Federation); A. Rembielińska, LOT Polish Airlines (Poland)
- 8243 1B **Nanostructure formation on lithium niobate surfaces by high-repetition rate sub-15-fs near-infrared laser pulses** [8243-48]
M. Straub, B. Weigand, K. König, Saarland Univ. (Germany)
- 8243 1C **Acoustic damage detection in laser-cut CFRP composite materials** [8243-49]
M. Nishino, Advanced Laser and Process Technology Research Association (Japan) and Mitsubishi Chemical Corp. (Japan); Y. Harada, T. Suzuki, H. Niino, Advanced Laser and Process Technology Research Association (Japan) and National Institute of Advanced Industrial Science and Technology (Japan)

- 8243 1D **Femtosecond laser hyperdoping and micro/nanotexturing of silicon for photovoltaics (Green Photonics Award Paper)** [8243-50]
B. Franta, M.-J. Sher, Y.-T. Lin, K. C. Phillips, E. Mazur, Harvard Univ. (United States)
- 8243 1E **Generation of new nanostructures in designed matrix by interfering femtosecond laser processing** [8243-51]
K. Momoo, K. Sonoda, Y. Nakata, N. Miyanaga, Osaka Univ. (Japan)
- 8243 1F **High-aspect ratio of near-field nano-lens for deep nano-crater patterning** [8243-52]
I. Fujimura, M. Terakawa, Keio Univ. (Japan)

Author Index

Conference Committee

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Monnet Saint-Etienne (France)
Koji Sugioka, RIKEN (Japan)

Session Chairs

- 1 Direct Writing
Xianfan Xu, Purdue University (United States)
Hiroyuki Niino, National Institute of Advanced Industrial Science and Technology (Japan)
- 2 Fundamental Aspects of Laser-Material Interaction
Hiroyuki Niino, National Institute of Advanced Industrial Science and Technology (Japan)
Xianfan Xu, Purdue University (United States)
- 3 Laser Modification of Materials
Guido Hennig, Daetwyler Graphics AG (Switzerland)
Bo Gu, IPG Photonics Corporation (China)
- 4 Laser Nanoscale Materials Processing and Manufacturing: Joint Session with Conference 8245
Richard F. Haglund, Jr., Vanderbilt University (United States)
- 5 Ultrafast Laser 3D-Fabrication: Joint Session with Conference 8247
Yoshiki Nakata, Osaka University (Japan)
Beat Neuenschwander, Berner Fachhochschule Technik und Informatik (Switzerland)
- 6 Ultrafast Laser-induced Modification of Glasses or Transparent Materials: Joint Session with Conference 8247
Stefan Nolte, Friedrich-Schiller- Universität Jena (Germany)
- 7 Ultrafast Laser Surface Processing: Joint Session with Conference 8247
Beat Neuenschwander, Berner Fachhochschule Technik und Informatik (Switzerland)
Yoshiki Nakata, Osaka University (Japan)
- 8 Fundamentals and Diagnostics in Ultrafast Laser Processing: Joint Session with Conference 8247
Michel Meunier, Ecole Polytechnique de Montréal (Canada)
- 9 Laser Surface Texturing/Polishing
Stephan W. Roth, BLZ Bayerisches Laserzentrum GmbH (Germany)
- 10 Laser Surface Texturing and 3D Microstructuring
Stephan W. Roth, BLZ Bayerisches Laserzentrum GmbH (Germany)

- 11 Novel Laser Systems and Optics for Laser Micro/Nanomachining
Bo Gu, IPG Photonics Corp. (China)
Guido Hennig, Daetwyler Graphics AG (Switzerland)
- 12 Photovoltaics: Joint Session with Conference 8244
Rainer Kling, ALPhANOV (France)

